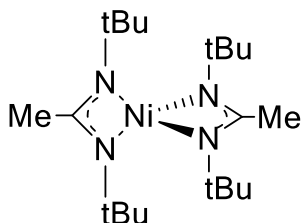


Catalog # 28-0045 Bis(N,N'-di-t-butylacetamidato)nickel(II), (99.999%-Ni) PURATREM



Thermal Behavior:

- Vapor pressure plot available in [1]; ~140 mTorr at 70 °C [3, 8, 10, 12]
- TGA available in [1]
- Sublimation: 95 °C at 0.05 Torr [1]
- Melting point: 87 °C [1]
- Decomposition at 250 °C in deposition process [12]

Technical Notes:

1. Nickel amidinate precursor for the growth of nickel containing thin films.

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
Ni	AACVD	150 °C in tetradecane	10 Torr	NH ₃ , H ₂	160 °C	[5]
NiO _x	ALD	20-135 °C		H ₂ O	90-250 °C	[2, 9, 11, 12, 14]
NiN _x	AACVD	150 °C in tetralin	1-10 Torr	NH ₃ , H ₂	160-240 °C	[1]
NiS _x	ALD	70-120 °C	0.3-0.6 Torr	H ₂ S	90-300 °C	[3, 4, 8, 10, 13]
NiS	PEALD		0.09 Torr	H ₂ S plasma	80-280 °C	[6]
NiC _x	PEALD	75 °C		H ₂ plasma	75-300 °C	[7]

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